

curriculum vitae

Dott. Mello Domenico



Work experience

Dates	2004-2022
Occupation or position held	Physics Laboratory Manager and Technical Staff Senior Member
Main activities and responsibilities	Catania physics laboratory technical and scientific coordination. This Physics Laboratory is an advanced and interdivisional laboratory that provides strategic support to the departments of Research and Development, Process Engineering, Product Engineering, Quality Assurance and Customer Complaint within the field of Chemical and Morphological Characterisation, Fault Isolation and Advanced in-line monitoring.
Name and address of employer	STMicroelectronics, Stradale Primosole, 50 I-95121 Catania ITALY
Type of business or sector	Semiconductor Factory
Dates	2002-2004
Occupation or position held	Micro-Analysis Group Team Leader
Main activities and responsibilities	Technical and scientific coordination of a Micro Analysis Group within the same laboratory. The Micro Analysis Group consisted of TEM, FIB and AFM and was in charge of two principle activities: advanced characterisation, performed mainly with TEM or manually prepared samples, or by FIB, and Advanced Process Control (APC). APC activity in particular is based on the study of critical process step and introduction of controls that is in turn based on the measurement of buried levels or complex structural characterisation.
Name and address of employer	STMicroelectronics, Stradale Primosole, 50 I-95121 Catania ITALY
Type of business or sector	Semiconductor Factory
Dates	2001-2002
Occupation or position held	Failure Analysis Engineer
Main activities and responsibilities	Characterisation using TEM techniques of simple structures on manually prepared samples utilising face-to-face gluing and mechanical polishing methods. During this period, the TEM team was comprised of one technician and myself.
Name and address of employer	STMicroelectronics, Stradale Primosole, 50 I-95121 Catania ITALY
Type of business or sector	Semiconductor Factory
Dates	2001-2002
Occupation or position held	Process engineer
Main activities and responsibilities	Process engineer in the 8" production line of the STMicroelectronics Catania site. I was particularly involved in the Rapid Thermal Process (RTP) and Metal Deposition Layer by PVD.
Name and address of employer	STMicroelectronics, Stradale Primosole, 50 I-95121 Catania ITALY
Type of business or sector	Semiconductor Factory
Dates	1998
Occupation or position held	Continuous and Coordinated Collaboration Agreement
Main activities and responsibilities	Researcher in surface analysis group under the D-SIMS (Dynamic-Secondary Ion Mass Spectroscopy) spectroscopy.

Name and address of employer	PASTIS Centro Nazionale per la Ricerca e lo Sviluppo dei Materiali S. C. p A. SS 7 "Appia" Km706 I-72100 Brindisi ITALY
Type of business or sector	Parco Scientifico e Tecnologico (Scientific and Technological Park)
Dates	1996 – 1998
Occupation or position held	Complementary Officer
Main activities and responsibilities	I fulfilled my military service as a Complementary Officer having won a public competition for the 166 th Course AUC (Cadets) that I attended at the SACA (School of Artillery Anti-Aircraft) I was nominated Second Lieutenant and assigned to the Alpine Brigade "JULIA" at the 3 rd Regiment of Mountain Artillery.
Name and address of employer	Ministero della Difesa (Ministry of Defence)
Type of business or sector	Military Service
Education and training	
Dates	1998 – 2000
Title of qualification awarded	PhD
Principal subjects/Occupational skills covered	Philosophy Doctor in "Materials Engineering" that involved discussing a thesis titled "Experimental study and application of ion implantation for industrial cutting tool treatment". During this period, I extensively studied the ion implantation process and relative process control on a cutting tool such as cutting fellow, gear shaper cutters, gear hobs etc. thereby expanding my knowledge in micro analysis (SIMS techniques in particular) and tribology testing.
Name and type of organisation providing education and training	Università degli Studi di Lecce
Dates	1989 – 1996
Title of qualification awarded	Degree in Physics
Principal subjects/Occupational skills covered	Degree in Physics discussing a thesis titled "Methods of imaging elaboration in electron microscopy" in which I experimentally tested noise reduction methods in reciprocal space for HRTEM images. During my degree thesis I acquired knowledge of TEM, image elaboration and structural characterisation at the nano-metric level. Degree vote 105/110.
Name and type of organisation providing education and training	Università degli Studi di Lecce (University of Studies, Lecce, ITALY)
Dates	1983 – 1988
Title of qualification awarded	High School Diploma
Principal subjects/Occupational skills covered	Scientific High School Diploma achieved with a score of 52/60
Name and type of organisation providing education and training	Liceo Scientifico "Banzi" Piazza Palio 63,I-73100 Lecce ITALY
Scientific Activity	<p>Patents</p> <p>US11133424B2 "M. C. Mazzillo, <u>D. P. Mello</u>, P. P. Barbarino, A. Sciuto "Low Power Optical Sensor for industrial and automotive application" (2021)</p> <p>Scientific Publications</p> <p>Antonella Sciuto , Lucia Calcagno, Massimo Mazzillo, <u>Domenico Mello</u>, Pietro Paolo Barbarino, Massimo Zimbone, and Giuseppe D'Arrigo "4H-SiC p-n Junction-Based Near IR Photon Source" IEEE SENSORS JOURNAL, VOL. 21, NO. 2, JANUARY 15, 2021</p>

G. D'Arrigo, M. Scuderi, A. Mio, G. Favarò, M. Conte, A. Sciuto, M. Buscema, G. Li-Destri, E. Carria, D. Mello, M. Calabretta, A. Sitta, J. Pries, E. Rimini "Mechanical characterization and properties of continuous wave laser irradiated Ge 2 Sb 2 Te 5 stripes" *Materials and Design* 202(8):109545 February 2021

Enrico Greco, Stefano Andrea Balsamo, Giuseppe Maccarrone, Domenico Mello, Enrico Ciliberto, Jing Shang, Tong Zhu "Gold-core lithium-doped titania shell nanostructures for plasmon-enhanced visible light harvesting with photocatalytic activity" *J Nanopart Res* 22:164 (2020)

A. Severino, D. Mello, S. Boninelli, F. Roccaforte, F. Giannazzo, P. Fiorenza, C. Calabretta, L. Calcagno, N. Piluso, G. Arena "Effects of Thermal Annealing Processes in Phosphorous Implanted 4H-SiC Layers" *Materials Science Forum* ISSN: 1662-9752, Vol. 963, pp 407-411 (2019)

Massimo Mazzillo, Domenico Mello, Pietro Paolo Barbarino, Vincenzo Vinciguerra, Giorgio Fallica Sebania Libertino, Antonella Sciuto, Salvatore Lombardo "*Silicon Photomultipliers with Embedded Optical Filters for Wearable Healthcare Applications*" *SENSORS*, 2017 IEEE (DOI: 10.1109/ICSENS.2017.8234373 1 Nov. 2017)

D. Mello, M. Nacucchi, G. Anastasi, M. Sacchi, R. Ricciari, E. Burrelli, L. Tapfer "New approach in Auger elemental relative sensitive factor calculation by using TEM-EDS analysis based on bi-layers of pure elements" *Ultramicroscopy* 193 143–150 (2018)

A. Sciuto, M. Mazzillo, P. Lenzi, S. Di Franco, D. Mello, P. P. Barbarino, G. Longo, S. Cascino, A. Santangelo, S. Albergo, A. Tricomi, O. Starodubtsev, O. Adriani, and G. D'Arrigo "Fully Planar 4H-SiC Avalanche Photodiode With Low Breakdown Voltage" *IEEE SENSORS JOURNAL*, VOL. 17, NO. 14, JULY 15, 2017

M. Mazzillo, D. Mello, P. P. Barbarino, M. Romeo, Y. Musienko, A. Sciuto, S. Libertino, S. Lombardo, and G. Fallica "*Noise Reduction in Silicon Photomultipliers for Use in Functional Near-Infrared Spectroscopy*" (*IEEE TRANSACTIONS ON RADIATION AND PLASMA MEDICAL SCIENCES*, VOL. 1, NO. 3, MAY 2017)

M. Ahmed Ali, M. Fouad Ali, E. Ciliberto, E. Greco, D. Mello, E. Viscuso "A new method for the preparation of gelatin nanolayer: a possible approach to the in situ consolidation of damaged gelatin photographic emulsions" *Applied Physics A*, V.122 (2016) 552

D. Mello a, R. Ricciari, A. Battaglia, M. Foti, C. Gerardi "Case study of failure analysis in thin film silicon solar cell" (*Microelectronics Reliability* **55** (2015) 1800–1803)

R. Ricciari, E.P. Ferlito, G. Pizzo, M. Padalino, G. Anastasi, M. Sacchi, G. Pappalardo, C. Consalvo, D. Mello "Auger electron spectroscopy characterization of Ti/NiV/Ag multilayer back-metal for monitoring of Ni migration on Ag surface" (*Microelectronics Reliability* **55** (2015) 1617–1621)

V. Giuffrida, P. Barbarino, G. Muni, G. Calvagno, G. Latteo, D. Mello "Fault isolation in a case study of failure analysis on Metal–Insulator–Metal capacitor structures" (*Microelectronics Reliability* **55** (2015) 1640–1643)

E. P. Ferlito, R. Ricciari, S. Grasso, A. Battaglia, D. Mello and C. Gerardi. "Determination of Mg Concentration and Distribution in Mg_xZn_{1-x}O Films Method for Solar Cell Application" *Surf. Interface Anal.* V. **46**, Issue 10-11 Pages 823–826 (2014)

G. Calvagno, G. Muni, A. Jossa, D. Mello "*Sample Preparation methodology for ultra thin oxide damage in Metal–Insulator–Metal capacitors*" (*Microelectronics Reliability* **52**, Issues 9–10, Pages 2064-2067 [2012])

M Nacucchi, M Alvisi, D Altamura, V Pfister, D Valerini, D Mello and C Giannini "*Experimental check of the use of unconventional reference materials for EDS analysis in a TEM by extrapolation method based on pure elements*" (*Materials Science and Engineering* **32**, 012017 [2012])

D. Mello, C. Coccorese, E. Ferlito, G. Sciuto, R. Ricciari, P. Barbarino, and M. Astuto "*Effect of weak metallic contamination on silicon epitaxial layer and gate oxide integrity*" (*Crystal Research and Technology*, DOI 10.1002/crat.201000585, 1 – 4, [2011])

E.P. Ferlito, S. Alnabulsi, D. Mello "A different approach in sample preparation method for metallic contamination study by ToF-SIMS and TXRF" (Applied Surface Science, **257**, 9925–9930 [2011])

D. Mello, R. Ricciari, M. Aiello, M. Astuto "Case study: Failure analysis for metal corrosion induced by pressure pot test" (Microelectronics Reliability **50**, 1436–1440, [2010])

C. Gerardi, V. Ancarani, R. Portoghese, S. Giuffrida, M. Bileci, G. Bimbo, O. Brafa, D. Mello, G. Ammendola, E. Tripiciano, R. Pugliesi and S. Lombardo, "Nanocrystal Memory Cell Integration in a Stand-Alone 16-Mb NOR Flash Device" (IEEE Transactions on electron devices **54**, 1376-1383 [2007])

C. Gerardi, S. Lombardo, G. Ammendola, G. Costa, V. Ancarani, D. Mello, S. Giuffrida, M. Plantamura, "Study of nanocrystal memory integration in a Flash-like NOR device" (Microelectronics Reliability **47**, 593-597 [2007])

R. Ricciari, M. Bertini, E. Ferlito, G. Pizzo, G. Anastasi, D. Mello, G. Franco, "Ion implanters contamination on wafer surface analyzed by ToF-SIMS and SPV analytical techniques" (Nuclear Instruments and Methods in Physics Research B **257**, 257–260 [2007])

D. Mello, Z. DeSouza, F. Giarrizzo, C. Gagliano, G. Franco, "Advanced strategy for in-line process monitoring using FIB and TEM", Nuclear Instruments and Methods in Physics Research B, **257**, 805–809 [2007])

D. Mello, F. Cordiano, A. Gerosa, M. Padalino, C. Gagliano, G. Renna, G. Franco, "In-line monitor introduction to prevent metallic contamination in wet bench" (Solid State Phenomena, **108-109**, 637-642 [2005])

M. Sciuto, L. Papalino, C. Gagliano, M. Padalino, C. Coccorese, D. Mello, G. Renna and G. Franco, "Deposition pressure influence on morphological and electrical properties of poly-silicon" (Crystal Research and Technology, **40**, 955-957 [2005])

D. Mello, L. Mirengi, R. Falcone and C. Esposito, "SIMS Study of TiN carbon implanted at high-dose." (Nuclear Instruments and Methods in Physics Research B, **226**, 376-384 [2004])

Carnabuci, C. Consalvo, D. Mello, A. Puglisi, M. Sacchi, A. Scanni, L. Trifoglio, A. Sidhwa "Elimination of Aluminum Bubble Defects from Interconnect Metal lines for 0.13 μ m Memory Devices " (VMIC Journal o IEEE Journal, [2004])

Carnabuci, C. Consalvo, D. Mello, A. Puglisi, M. Sacchi, A. Scanni, A. Sidhwa, L. Trifoglio, "The Impact from the Titanium under Layer Film Thickness and the Thermal Budget Stress Generating Abnormal Aluminum Grains and Partial Voids in the Metal-1 Interconnect Lines" (VMIC Journal o IEEE Journal, [2004])

C. Consalvo, A. Privitera, D. Mello, A. Sidhwa, and L. Marzaioli "The Impact of Thermal Budget Causing High Via Resistance Failure for 0.18 μ m Memory" (VMIC Journal o IEEE Journal, [2003])

M. A. Tagliente, R. Falcone, D. Mello, C. Esposito and L. Tapfer, "On the influence of carbon implantation on the structural properties of hard TiN coatings studied by glancing-incidence x-ray diffraction" (Nuclear Instrument and Methods in Physics Research B, **179**, 42-54 [2001])

M. A. Tagliente, R. Falcone, D. Mello, C. Esposito and L. Tapfer, "Structural Properties of Carbon-Implanted TiN Coating by Glacing-Incedent X-Ray Diffrcion" (Materials Science Forum, **378-381**, 723-728 [2001])

R. Falcone, D. Mello, A. Passaro, V. Dattoma and C. Esposito, "Application of SIMS technique measuring the spatial distribution of the dose in N⁺ implantation into the internal surface of small hollow cylinders for wear reduction applications." (Surface and Interface Analysis **30**, 251-254 [2000])

R. Falcone, D. Mello, A. Passaro, V. Dattoma and C. Esposito, "Study of ion implantation treatment for wear reduction applications into the internal surface of an industrial bush" (Vuoto, **XXIX**, 8-10 [2000])

Proceedings

International Congress on Microscopy & Spectroscopy (2018)

D. Mello, M. Nacucchi, G. Anastasi, R. Ricciari, M. Sacchi, C. Consalvo, E. Burrese and L. Tapfer "New approach in Auger RSF calculation for precise quantitative Analysis using correlation with TEM-EDS analysis by extrapolation method based on pure elements"

12 European Conference on Silicon Carbide and Related Materials (2018)

A. Severino, D. Mello, S. Boninelli, F. Roccaforte, F. Giannazzo, P. Fiorenza, C. Calabretta, L. Calcagno, N. Piluso, G. Arena "Effects of Thermal Annealing Processes in Phosphorous Implanted 4H-SiC Layers"

26st European Symposium on Reliability of Electron Devices, Failure Physics and Analysis (2015)

D. Mello, R. Ricciari, A. Battaglia, M. Foti, C. Gerardi "Case study of failure analysis in thin film silicon solar cell"

R. Ricciari, E.P. Ferlito, G. Pizzo, M. Padalino, G. Anastasi, M. Sacchi, G. Pappalardo, C. Consalvo, D. Mello "Auger electron spectroscopy characterization of Ti/NiV/Ag multilayer back-metal for monitoring of Ni migration on Ag surface"

V. Giuffrida, P. Barbarino, G. Muni, G. Calvagno, G. Latteo, D. Mello "Fault isolation in a case study of failure analysis on Metal-Insulator-Metal capacitor structures"

E-MRS Spring Meeting 2015 - SYMPOSIUM WB

MahaAhmed Ali ,Enrico Ciliberto, Mona Fouad Ali , Enrico Greco ,Domenico Mello, Ezio Viscuso "A New Method for the Preparation of Gelatin Nanolayer: A Possible Approach to the in-situ Consolidation of Damaged Gelatin Photographic Emulsions"

15th European Conference on Applications of Surface and Interface Analysis (ECASIA 2013)

E. P. Ferlito, R. Ricciari , S. Grasso, A. Battaglia, D. Mello and C. Gerardi. "Determination of Mg Concentration and Distribution in $Mg_xZn_{1-x}O$ Films Method for Solar Cell Application"

2013 IEEE International Reliability Physics Symposium (IRPS 2013)

E. P. Ferlito, G. Pizzo, R. De Gregorio G. Anastasi, R. Ricciari and D. Mello "TOF-SIMS Characterization of Boron and Phosphorus Distribution in sub-atmospheric Chemical Vapour Deposition Borophosphosilicate Glass (SA-CVD BPSG) films"

12th European Workshop on Modern Developments and Applications in Microbeam Analysis (EMAS 2011)

M. Nacucchi, M. Alvisi, D. Altamura, V. Pfister, D. Valerini, D. Mello and C. Giannini "Experimental validation of the use of unconventional reference materials for EDS analysis in a TEM"

International conference on Materials for Advance Technologies (ICMAT 2011)

D. Mello, R. Ricciari, M. Astuto and CT Yong "Case studies of advanced failure analysis and reliability in semiconductor manufacturing"

21st European Symposium on Reliability of Electron Devices, Failure Physics and Analysis (2010)

D. Mello, R. Ricciari, M. Aiello, M. Astuto "Case study: Failure analysis for metal corrosion induced by pressure pot test"

14th European FIB Users Group Meeting (EFUG2010)

F. Giarrizzo, S. Damigella, G. Mazzaglia and D. Mello "In-line, non destructive, and direct measurement performed by FIB in semiconductor manufacturing environments"

G. Anastasi, F. Giarrizzo and D. Mello "*Mixed technique for TEM sample preparation on device having SiC substrate*"

ICG Italian Crystal Growth (2010)

D. Mello, C. Coccorese, E. P. Ferlito, G. Sciuto, R. Ricciari, M. Astuto "*Effect of weak metallic contamination on Silicon epitaxial layer and gate oxide integrity*"

C. Coccorese, D. Mello, G. Morale, G. Anastasi, G. Privitera "*Ion implantation defects recovery after boron high fluence, high energy implant*"

D. Mello, G. Sciuto, P. Prete, N. Lovergine "*Different approach to the TEM sample preparation of semiconductor nanowires using dual-beam FIB*"

10th AEC-APC European Advanced Process Control and Manufacturing Conference (2010)

R. Ricciari, M. R. Salvo, E. P. Ferlito, M. Padalino, G. Pizzo, C. Gagliano, C. Consalvo, D. Mello "*TiN CVD oxygen contamination monitoring by AES as standard process control in manufacturing environment*"

D. Mello, C. Consalvo, F. Giarrizzo, A. Puccia "*In-line, non destructive, and direct AlCu film thickness measurement by FIB in semiconductor manufacturing environment*"

IEEE International Electron Device Meeting (IEDM 2008)

C. Gerardi, G. Albin, A. Emmi, E. Tripiciano, O. Fiore, D. Mello, G. Anastasi, C. Gagliano, G. Iacono, A. Maurelli, G. Molas, M. Gely and B. De Salvo "*Performance and reliability of a 4Mb Si nanocrystal NOR Flash memory with optimized 1T memory cells*"

14th Workshop on Dielectrics in Microelectronics (WoDIM 2006)

C. Gerardi, S. Lombardo, G. Ammendola, G. Costa, V. Ancarani, D. Mello, O. Brafa-Musicoro, and C. Plantamura, "*Study of Nanocrystal Memory Integration in a 16-Mb Flash-like NOR Array*"

15th International Conference on Ion Beam Modification Materials (IBMM 2006)

R. Ricciari, M. Bertini, E. Ferlito, G. Pizzo, G. Anastasi, D. Mello, G. Franco, "*Ion implanters contamination on wafer surface analyzed by ToF-SIMS and SPV analytical techniques*"

D. Mello, Z. DeSouza, F. Giarrizzo, C. Gagliano, G. Franco, "*Advanced strategy for in-line process monitoring using FIB and TEM*"

Gettering and Defect Engineering in Semiconductor Technology (GADEST 2005)

D. Mello, F. Cordiano, A. Gerosa, M. Padalino, C. Gagliano, G. Renna, G. Franco, "*In-line monitor introduction to prevent metallic contamination in wet bench*"

International Symposium on Semiconductor Manufacturing (ISSM 2005)

G. Franco, Z. DeSouza, D. Mello, M. Weschler, "*An initial investigation into the use of focused ion beam technology for inline process control of critical dimensions in the FAB*"

XXXIV Congresso Nazionale Associazione Italiana di Cristallografia

M. Sciuto, L. Papalino, C. Gagliano, M. Padalino, C. Coccorese, D. Mello, G. Renna and G. Franco, "*Deposition pressure influence on morphological and electrical properties of Poly-silicon*"

13th European Microscopy Congress (EMC 2004)

D. Mello, M. Crispino, C. Consalvo, C. Gagliano, A. Privitera, F. Giarrizzo, A. Privitera and G. Franco, "*Case study: TEM, FIB and OBIRCH analysis of high resistance via Failures in 0.18μm flash memory devices due to non optimized thermal budget*"

21st International VLSI Multilevel Interconnection Conference (2004)

Carnabuci, C. Consalvo, D. Mello, A. Puglisi, M. Sacchi, A. Scanni, L. Trifoglio, A. Sidhwa "*Elimination of Aluminum Bubble Defects from Interconnect Metal lines for 0.13μm Memory Devices*"

Carnabuci, C. Consalvo, D. Mello, A. Puglisi, M. Sacchi, A. Scanni, A. Sidhwa, L. Trifoglio, "*The Impact from the Titanium under Layer Film Thickness and the Thermal Budget Stress Generating Abnormal Aluminum Grains and Partial Voids in the Metal-1 Interconnect Lines*"

20th International VLSI Multilevel Interconnection Conference (2003)

C. Consalvo, A. Privitera, D. Mello, A. Sidhwa, and L. Marzaioli "The Impact of Thermal Budget Causing High Via Resistance Failure for 0.18 μ m Memory"

204th The Electrochemical Society Meeting (ECS 2003)

M. Vulpio, D. Fazio, M. Bileci, D. Mello, C. Gerardi "Electrical and Physical Characterization of Cobalt Silicide Growth with Alternative Cap Layers"

E-MRS Spring Meeting 2003 - SYMPOSIUM I

D. Mello, D. Trapani, G. Franco, M.G. Grimaldi, "Titanium salicide phase Polymorphic transition study versus the bias polarization change applied to the substrate during the Ti starting films deposition"

7th European Powder Diffraction Conference

M. A. Tagliente, R. Falcone, D. Mello, C. Esposito and L. Tapfer, "Structural properties of carbon implanted TiN coatings studied by glancing-incidence x-ray diffraction"

XV Congresso Nazionale sulle Scienze e Tecnologie del Vuoto.

D. Mello, L. Mirengi, R. Falcone, and C. Esposito, "SIMS studies of TiN hard coatings Carbon implanted for an industrial component."

8th European Conference on Applications of Surface and Interface Analysis "ECASIA '99".

R. Falcone, D. Mello, L. Mirengi and C. Esposito, "Carbon implanted TiN hard coatings studied by SIMS and XPS techniques"

R. Falcone, D. Mello, A. Passaro, V. Dattoma and C. Esposito, "Application of SIMS technique measuring the spatial distribution of the dose in N⁺ implantation into the internal surface of small hollow cylinders for wear reduction applications".

Personal skills and competences

Mother tongue(s)

Other language(s)

Self-assessment

European level (*)

English**French****Italian**

Understanding		Speaking		Writing
Listening	Reading	Spoken interaction	Spoken production	
B2 Independent user	B2 Independent user	B2 Independent user	B2 Independent user	B2 Independent user
B2 Independent user	B2 Independent user	B2 Basic user	B2 Basic user	B2 Basic user

(*) Common European Framework of Reference (CEF) level

Social skills and competences

Working in not homogeneous and multi-ethnic groups with different methodological approach has allowed me to increase innate interpersonal skills and decision-making.

Attending to projects inter-divisional and intercontinental aimed at qualification of new processes I have acquired the ability to work remotely without lose focus on time, quality of results.

At the goals achievement it has contributed to be a member of the Failure Analysis Network which is a network of internal lab ST aims to standardize the indicator parameters, the sharing of expertise in order to address the customer requests resulting in reduction of cycle time.

Organisational skills and competences

The current position, that involves the coordination of 19 head, has enhanced the possibility of the application of management instruments in order to lead a team in stressful situations especially related to management priorities, the relationship with customers and deadlines of work activities

I was trainers for the steps of "Physical Identification" of course "Failure Analysis" in ST University, which is an organization responsible for the training of people inter-site initially, but today only on site, I have completed and increased my ability to manage complexity

Technical skills and competences

I acquired technical skills in analysis types such as SEM, TEM, FIB, AFM, AES, ToF-SIMS, D-SIMS, SRP, TXRF, EDX, EELS and good knowledge of Fault Isolation techniques such as OBIRCH, EMMI and OBICH.

Computer skills and competences

Excellent knowledge of DOS, WINDOWS and UNIX operative systems and FORTRAN, QUICK BASIC, COBOL e C programming languages.

